

ABSTRACT

Polymerizable silicon-containing compounds of formula
5 (1) wherein R¹ is hydrogen, halogen or monovalent organic
group are polymerized into polymers. A resist composition
comprising the polymer as a base resin is sensitive to
high-energy radiation, has excellent sensitivity and
resolution at a wavelength of less than 300 nm, and high
10 resistance to oxygen plasma etching, and thus lends itself to
micropatterning for the fabrication of VLSIs.

